

ABSTRACT

A substrate cleaning apparatus (18) starts supply of a first rinse liquid to a surface (W1) of a substrate (W) from a rinse liquid nozzle (75). After formation of a liquid film for particle detachment on the surface (W1) of the substrate (W) with the first rinse liquid, dispensing of a jet flow of the cleaning liquid to the surface (W1) of the substrate (W) from the jet flow nozzle (72) is started, and movement of the cleaning arm (73) is started. Furthermore, after the movement of the cleaning arm (73) is started, supply of the second rinse liquid to the surface (W1) of the substrate (W) from the rinse liquid nozzle (75) is started, forming a liquid film for particle discharge on the surface (W1) of the substrate (W) with the second rinse liquid.

Fig. 1